

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATLY. DOCKET NO. M122-1829		SERIAL NO. Filed Herewith	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT H. Daniel Dulman		FILING DATE Filed Herewith	
				GROUP Unknown		11046 U.S. PTO 10/07/2440 02/05/02	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>JD</i>	AA	5,208,125	05/93	Lowrey et al.	430	5	
<i>JD</i>	AB	5,217,830	06/93	Lowrey	430	5	
<i>JD</i>	AC	5,308,721	05/94	Garofalo et al.	430	5	
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AM						
	AN						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
<i>JD</i>	AO		Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method",				
			19th Annual BACUS Sympos. on Photomask Technology, Monterey, CA, Sept. 1999, SPIE Vol. 3873, pp. 288-296.				
<i>JD</i>	AP		Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method (II)",				
			20th Annual BACUS Sympos. on Photomask Technology, Proceedings of SPIE Vol. 4186 (2001), pp. 801-809.				
<i>JD</i>	AQ		Lim, S. et al., "Application of Alternating Phase-Shifting Masks to Sub-Quarter Micron Contact Holes", SPIE Vol. 2726, Feb. 1996,				
			pp. 516-523.				
<i>JD</i>	AR		Lim, S. et al., "Application of Alternating Phase-Shifting Masks to 200nm Contact Holes", SPIE Vol. 2884, July 1996, pp. 243-254.				
EXAMINER <i>A. Zorawski</i>				DATE CONSIDERED <i>11/6/03</i>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							